

FESEM BOOKING FORM

CENTRE FOR FUNCTIONAL MATERIALS AND NANOTECHNOLOGY (CFMN)

Institute of Science Universiti Teknologi MARA 40450 Shah Alam , Selangor.

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A) APPLICANT'S INFORMATION												
NAM	E					STUDENT ID/ STAFF ID (UITM APPLICANT)						
TEL. N	O (DIRECTLINE, H/P)					EMAIL						
UNIVERSITY/FACULTY/ COMPANY ADDRESS												
STATI	JS	MASTER STUDENT PHD STUDENT RESEARCHER INDUSTRY OTHERS										
B) SUPERVISOR'S INFORMATION (UNIVERSITY'S APPLICANT ONLY)												
NAM	E					STAFF ID (UITM APPLICANT)						
TEL. N	O (DIRECTLINE, H/P)					EMAIL						
SUPERVISOR'S SIGNATURE & OFFICIAL STAMP						GRANT NO						
C) SAMPLE INFORMATION												
NO.	SAMPLE ID		CHEMICAL FORMULA	HAZARDOUS	TOXIC	CORROSIVE	HYGROSCOPIC	OTHER INFORMATION (e. g: type of sample: powder or thin film) (size thin film: 0.5 x 0.5cm)				
				(TICK	(TICK WHICH IS APPL							
For measurements please give additional details (if any):												
To Theasarchients please give additional details (ii dify).												
FESEM MEASUREMENT			UiTM		IPTA		IPT	S	INDUSTRY	TICK HERE (/)		
IMAGING (PER SAMPLE)			RM 250	RM 250		RM 300		400	RM 600			
IMAGING + EDX (PER SAMPLE)				RM 300		RM 350 RM		450	RM 750			
Declaration I/we hereby declared that the materials to be used with the machines/equipments have the PHYSICAL AND CHEMICAL property(s) as mention below. I and my supervisor will be held fully responsible for the damaged to the machine due to false declaration(s).												
I/we hereby acknowledge and agree with the charge of FESEM analysis imposed by CFMN, Institute of Science, UiTM.I/we will held the responsibility if the bursary fail to deduct from the research grant declared. For any decline or refused charge from the declared grant, the supervisor will be held the responsible for the settlement charge.												
_	Applicant's Signature:		<u>-</u>	Date:								
FOR OFFICE USE ONLY					TERMS & CONDITIONS							
APPLICATION STATUS: ACCEPT/REJECT DATE COMPLETED: COMMENTS: TOTAL CHARGE: SIGNATURE/DATE: RM			2. Th 3. M	 The sample must be very dry in order to be placed in high vacuum. Maximum of 3 samples only allowed for each application. 								
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